
Supporting Information

for

Polymer blend lithography: A versatile method to fabricate nanopatterned self-assembled monolayers

Cheng Huang^{1,2,3}, Markus Moosmann^{1,2}, Jiehong Jin^{1,2}, Tobias Heiler^{1,2},

Stefan Walheim^{*1,2} and Thomas Schimmel^{1,2}

Address: ¹Institute of Nanotechnology (INT), Karlsruhe Institute of Technology (KIT), 76021 Karlsruhe, Germany, ²Institute of Applied Physics and Center for Functional Nanostructures (CFN), Karlsruhe Institute of Technology (KIT), 76128 Karlsruhe, Germany and ³Joint Research Laboratory Nanomaterials Karlsruhe Institute of Technology (KIT)/Darmstadt University of Technology, 64287 Darmstadt, Germany

Email: Stefan Walheim* - stefan.walheim@kit.edu

*Corresponding author

Snow-jet treatment of FDTs-SAM

Stability of FDTs-SAM against snow-jet treatment

The AFM pictures below show the stability of the FDTs-SAM against snow-jet treatment. The left picture was taken after a soft treatment, which lasted for about 30 seconds, while the right one was treated for 5 minutes. Both of the pictures have a scanning range of $5 \times 5 \mu\text{m}$ and were taken in contact mode in water. The results show that there is no observable change of the depth of the holes after a thorough snow-jet treatment. This proves that the FDTs-SAM is stable against this lift-off method.

